



2024 Source Workshop - List of Accepted Papers

(Version September 16, 2024)

#	Paper #	Area	First Name	Last Name	Company	Paper Title
1	S1	Keynote	Jan	Van Schoot	ASML	2024 Source Workshop Keynote Presentation (Tentative Title)
1	S2	Keynote	Peter	Moulton	MIT LL	Solid state laser drivers for EUV plasma sources
1	S3	Keynote	Manuel	Guizar-sicairos	PSI	3D Nanotomography via Coherent X-ray Lensless Imaging
1	S4	Keynote	Torsten	Feigl	optiXfab	2024 Source Workshop Keynote Presentation (Tentative Title)
1	S5	Keynote	Konstantin	Koshelev	ISTEQ	Lithium, a “dream fuel” for actinic inspection?
2	S10	Modeling /Code Comparison	Howard	Scott	LLNL	2024 Code Comparison Summary
2	S11	Modeling /Code Comparison	Samuel	Totorica	PPPL	Kinetic Simulations of Ion Dynamics in Laser-Driven Tin Plasma EUV Sources
2	S12	Modeling /Code Comparison	Igor	Golvokin	Prizm Computations	2024 Code Comparison Results
2	S13	Modeling /Code Comparison	Akira	Sasaki	QST	2024 Code Comparison Results
3	S21	Lasers, HHG and Applications	Sven	Breitkopf	AFS (Trumpf)	High-Flux XUV Beamlines enabling photon-hungry imaging and spectroscopy methods
3	S22	Lasers, HHG and Applications	Bastian	Manschwetus	Class 5 Photonics	Recent advances on High-Brilliance EUV Sources based on high harmonic generation



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3 S23	Lasers, HHG and Applications	Thomas	Mezger	Trumpf	Ultrafast Thin-Disk Amplifiers and Nonlinear Pulse Compression
3 S24	Lasers, HHG and Applications	Oleg	Pronin	n2-Photonics GmbH	Pulse shortening with multipass cells
3 S25	Lasers, HHG and Applications	Jens	Limpert	Univ. of Jena	2 μ m wavelength fiber lasers for next generation EUV plasma sources
4 S31	EUVL Extension - Blue- X	Takeshi	Higashiguchi	Utsunomiya University	Recent progress of beyond EUV sources
4 S32	EUVL Extension - Blue- X	Brendan	Reagan	LLNL	Solid state $\lambda \approx 2 \mu\text{m}$ laser drivers for EUV lithography
4 S33	EUVL Extension - Blue- X	Kevin	Heidrich	xLight	A Path to 2000 W
4 S34	EUVL Extension - Blue- X	Ladislav	Pina	Rigaku	Grazing Incidence Optics Calculations for Plasma and 6.xx nm Coherent Beams
4 S35	EUVL Extension - Blue- X	Bjorn	Hegelich	TAU Systems / University of Texas at Austin	Industrialization of laser-driven accelerators and light sources
4 S36	EUVL Extension - Blue- X	Marcelo	Ackermann	University of Twente	2024 Source Workshop - Invited Presentation (Tentative Title)
5 S41	HVM EUV Sources	Jorge	Gonzales	ARCNL	Effect of target mass on CO ₂ -driven EUV emitting tin plasma for nanolithography
5 S42	HVM EUV Sources	Klaas	Bijlsma	University of Groningen	Electron capture in collisions of Sn ions with H ₂ molecules
5 S44	HVM EUV Sources	Yiming	Pan	Hokudai University	Investigation of laser-plasma interaction in a dual-pulse laser produce tin plasma



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5	S45	HVM EUV Sources	Mark	van de Kerkhof	ASML	Pulsed EUV induced plasma: fast transients, accumulation and hybrid 3D-PIC model
5	S46	HVM EUV Sources	Ahmed	Diallo	PPPL	Laser Plasmas Interactions for Microelectronics: Status Update
5	S47	HVM EUV Sources	Wang	Xinbing	Huazhong University of Science & Technology	Laser produced tin droplet plasma interference diagnosis and droplet deformation study
5	S48	HVM EUV Sources	Hakaru	Mizoguchi	Kyushu university	Plasma Dynamics and Future of LPP-EUV Source for Semiconductor Manufacturing II
5	S49	HVM EUV Sources	Job	Beckers	TU Eindhoven	Plasma-particle Interaction under conditions relevant to EUV Lithography
5	S50	HVM EUV Sources	Dion	Engels	ARCNL	Spectroscopic Imaging of Tin Gas Vaporized Near Plasma Threshold
5	S51	HVM EUV Sources	Felix	Kohlmeier	ARCNL	Power Partitioning Reconstruction for Laser Produced Plasmas
6	S61	Metrology Sources	David	Reisman	Energetiq	Next-Generation Discharge-Produced Plasma (DPP) EUV Source
6	S62	Metrology Sources	Fumio	Iwamoto	Gigaphoton	Development progress of Gigaphoton's Sn-LPP
6	S63	Metrology Sources	Keitaro	Hayashida	Laseretec	Status update of EUV light source development for inspection tools
6	S64	Metrology Sources	Peter	Smorenburg	ASML	XUV light sources for semiconductor metrology
6	S65	Metrology Sources	Yusuke	Teramoto	Ushio	A compact laser-driven short-wavelength radiation source



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7 S71	Optics and Metrology	Sascha	Brose	RWTH	Ultra-compact inline transmission grating spectrograph for EUV wavelengths
7 S72	Optics and Metrology	Analia	Fernande	PTB	From EBL Gratings to Advanced Photonics for the inspection of Complex Nanostructures
7 S73	Optics and Metrology	Lucas	Poirier	TNO	EUV-sources for optics-lifetime and materials testing
7 S74	Optics and Metrology	Muharrem	Bayraktar	University of Twente	EUV source metrology using transmissive and diffractive optics
7 S75	Optics and Metrology	Martin	Wünsche	Indigo Optics	EUV Reflectometry and Non-Destructive Nanoscale
7 S76	Optics and Metrology	Linus	Nagel	RWTH	Extreme ultraviolet high intensity exposure setup for small-spot in-band exposures
7 S77	Optics and Metrology	Peter	Kraus	ARCNL	How can we achieve at-resolution metrology in optical microscopy?
9 S81	Poster	Abdul	Rehman	Univ of Twente	Predicting the chemical stability of thin film coatings in hydrogen for EUV applications
9 S82	Poster	Duncan	Ramsamoedj	Univ of Twente	Investigating EUV degradation with in-situ EUV transmission measurements
9 S83	Poster	Tatsuya	Soramoto	Utsunomiya University	Short-wavelength EUV source by a continuous liquid bismuth jet
9 S84	Poster	Tsakasa	Sugiura	Utsunomiya University	Enhancement of the EUV conversion efficiency using multiple-solid-state-laser pulse
9 S85	Poster	Karl	Shubert	ARCNL	Observation of Surface Modulation on Free-Flying Liquid Metal Sheets



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9	S87	Poster	TBA	TBA	Energetiq	2024 Source Workshop Poster Presentation (Tentative Title)
9	S88	Poster	Moinuddin	Kadiwala	Helmut-Schmidt-Universität	High Harmonic Generation with a compact amplification-free thin-disk laser-oscillator system
9	S89	Poster	Chun-Tse	Wu	National Central University	Numerical Study of Laser-Produced Plasma Light Source on Improving Conversion Efficiency by Three Pulse Scheme
9	S90	Poster	Ismael	Gisch	RWTH	Broadband reflective spectrometer for high-resolution spectral characterization of radiation sources
9	S91	Poster	Alexander	Tovstopyat	ISTEQ Group	LEUS: A Novel LPP EUV Light Source with Fast-Rotating Lithium Target and Unique Spectral Brightness